



REPLACEMENT SHEET

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FIG. 1

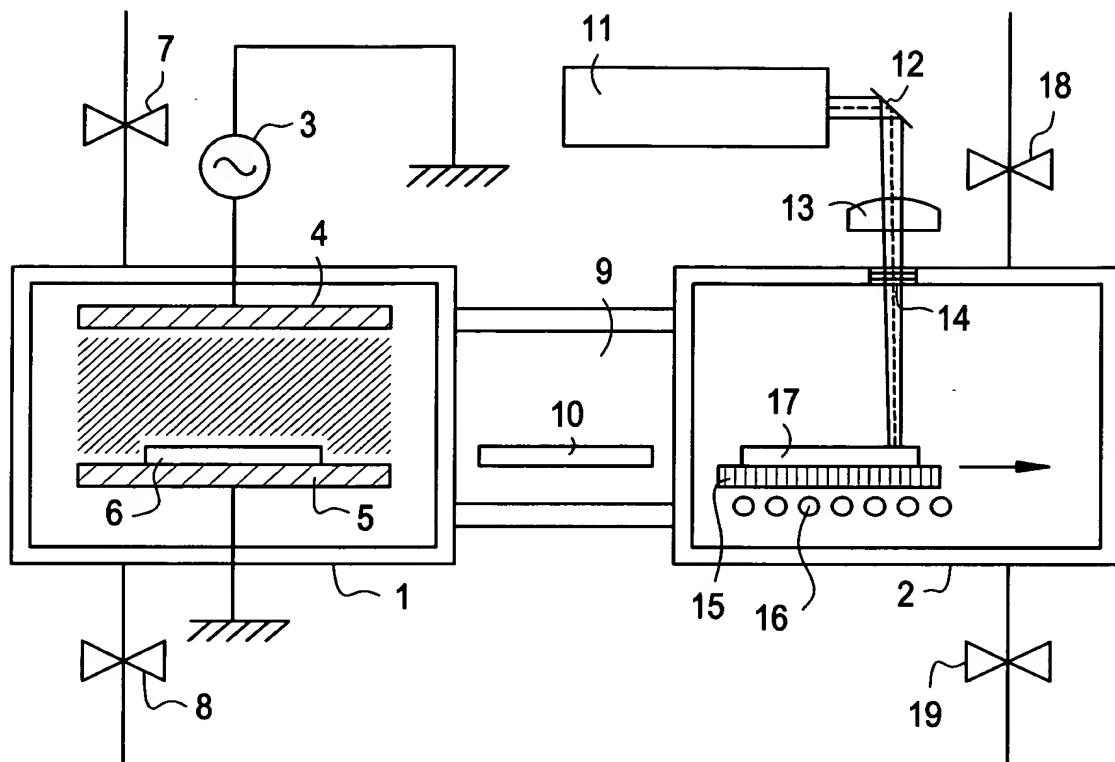
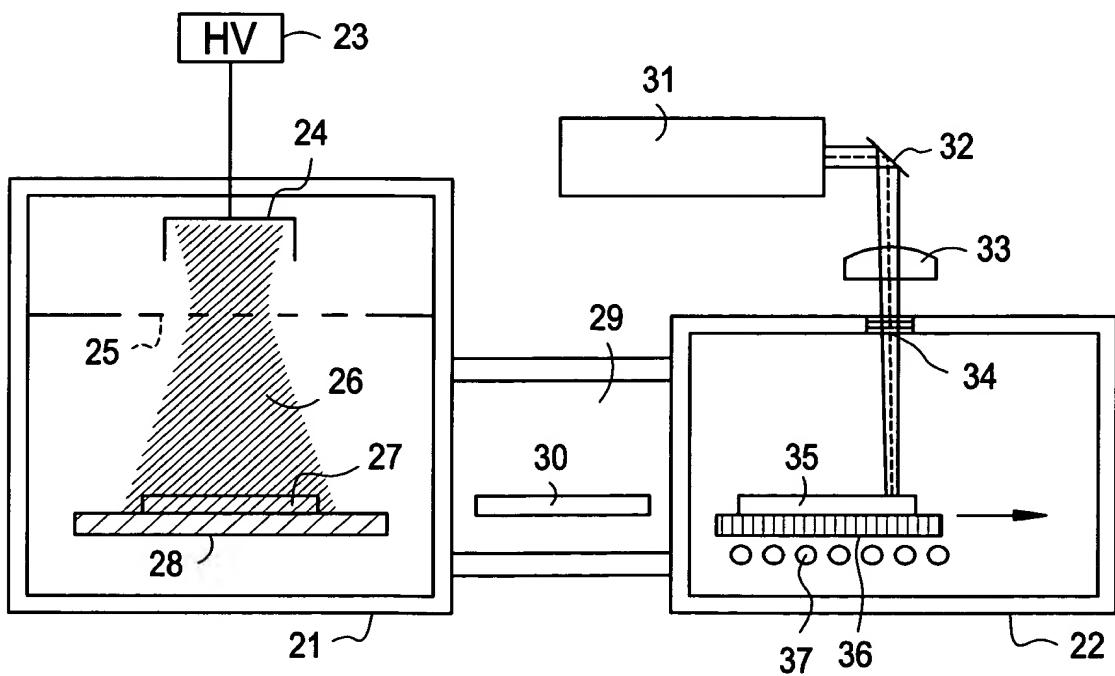


FIG. 2



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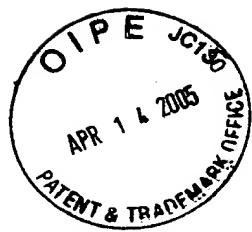
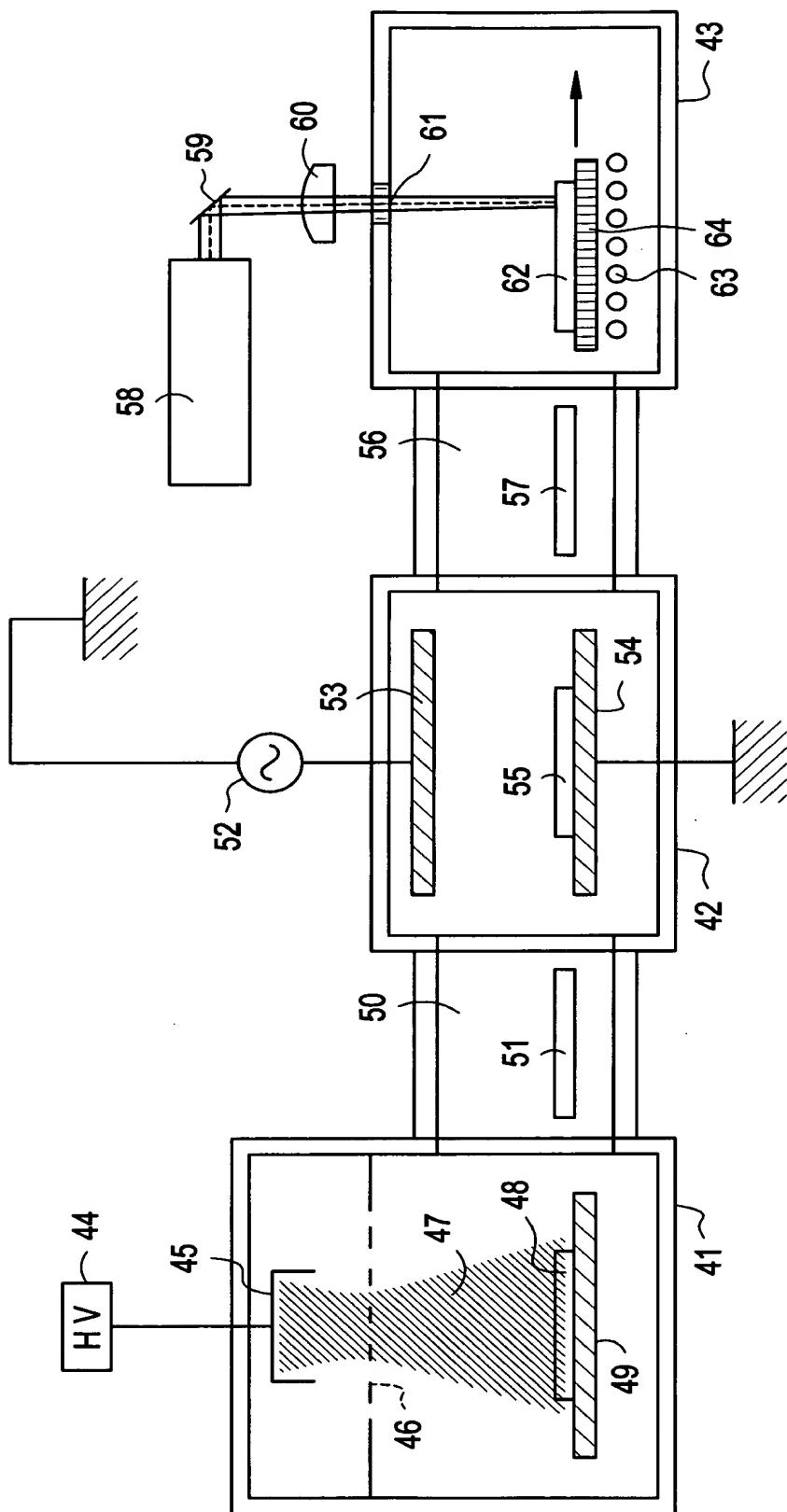


FIG. 3

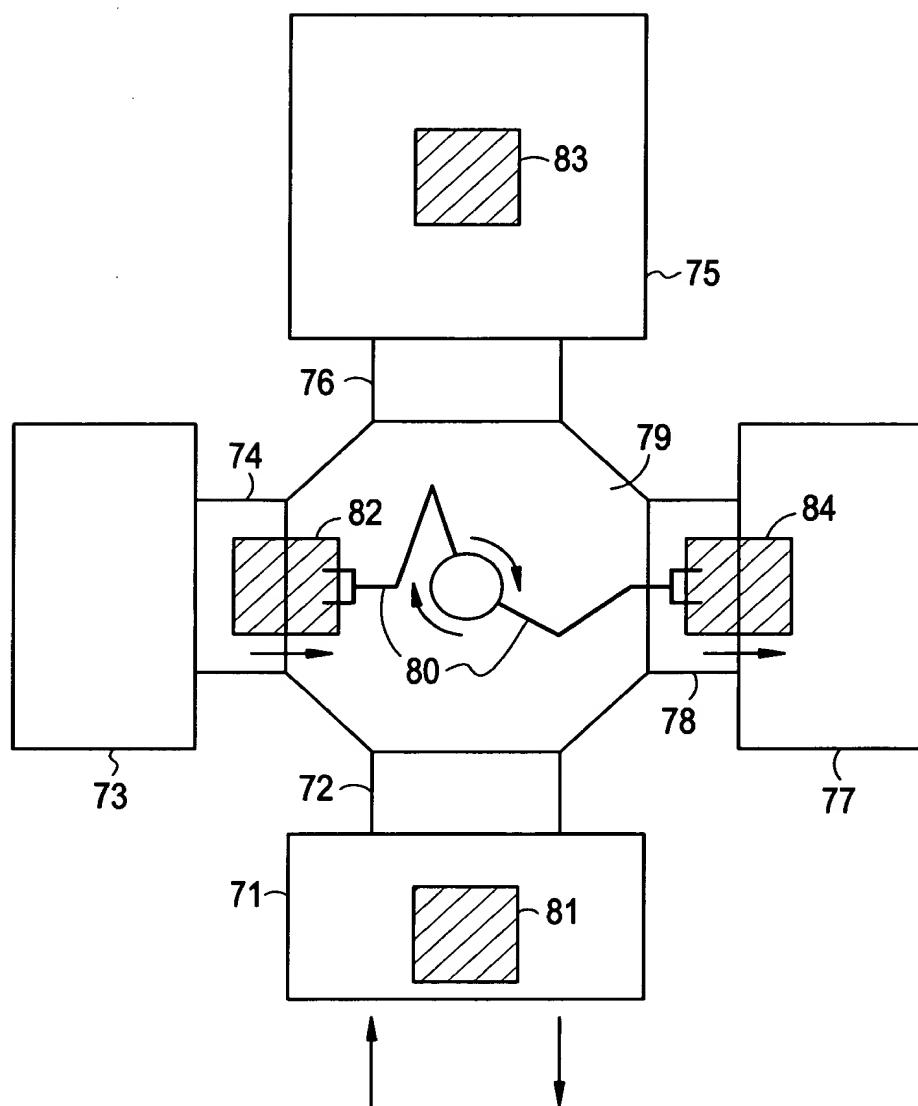


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FIG. 4





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FIG. 5A

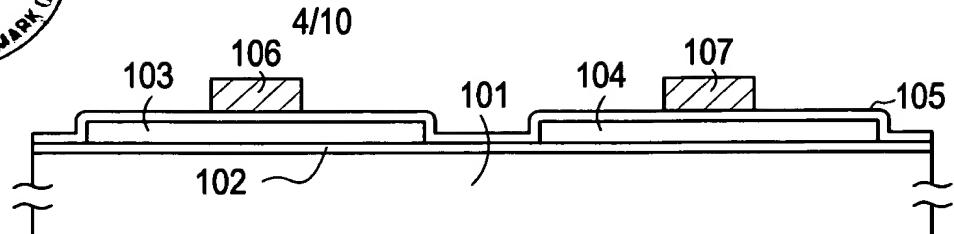


FIG. 5B

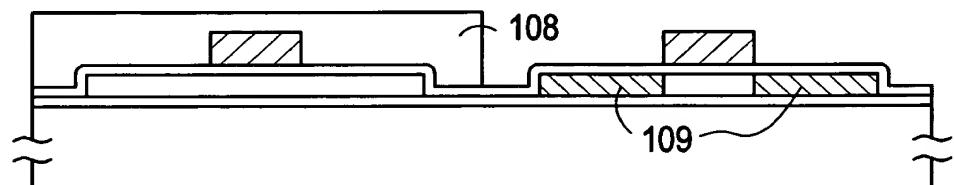


FIG. 5C

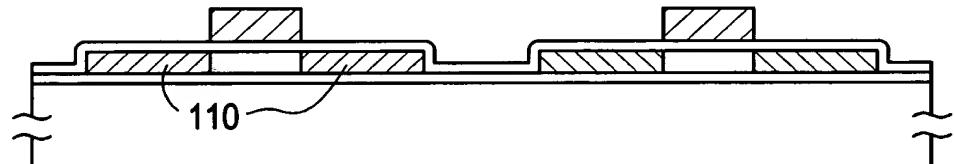


FIG. 5D

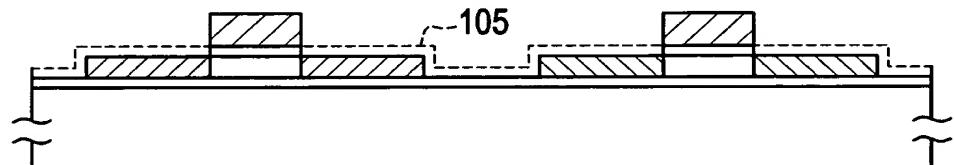


FIG. 5E

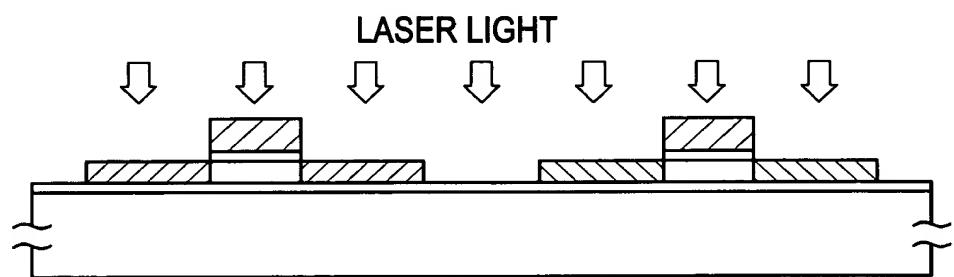
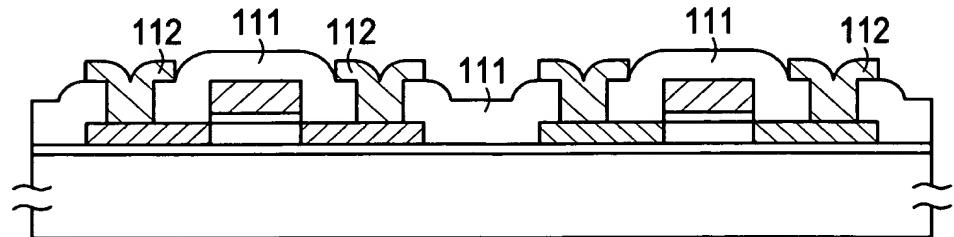
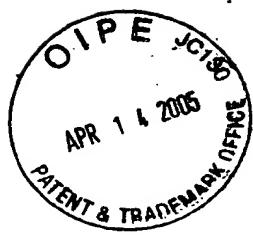


FIG. 5F

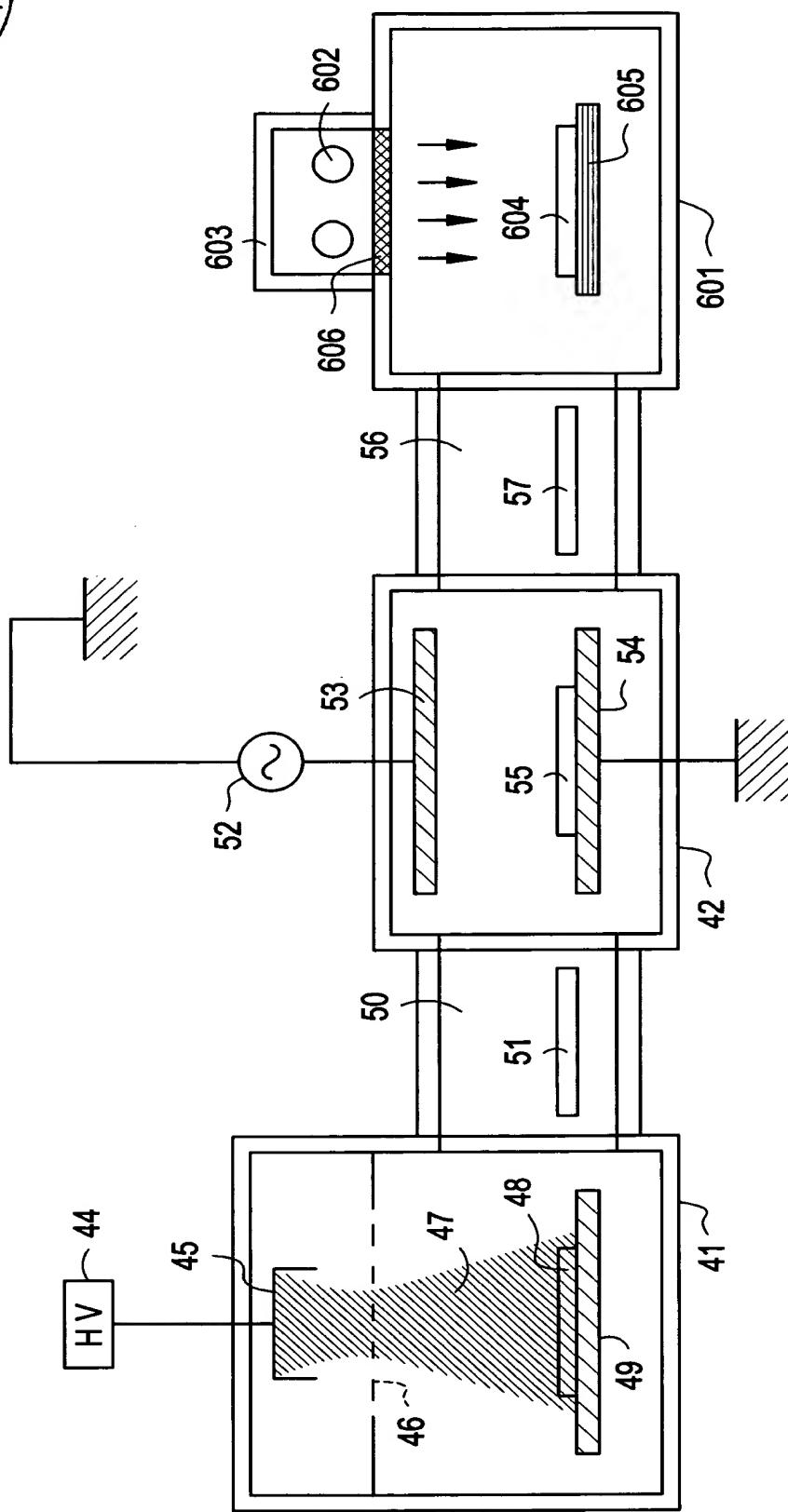


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FIG. 6





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FIG. 7A

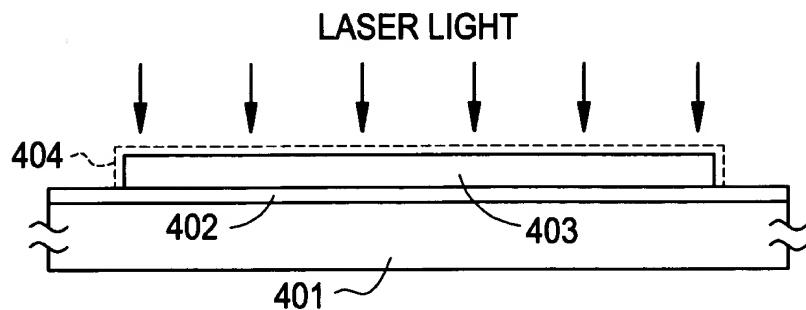


FIG. 7B

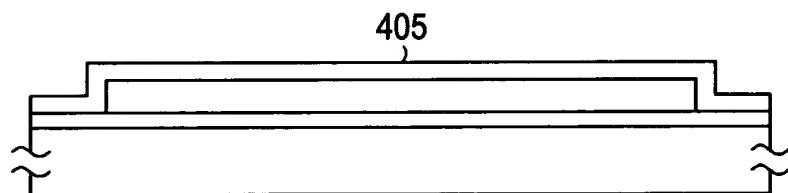


FIG. 7C

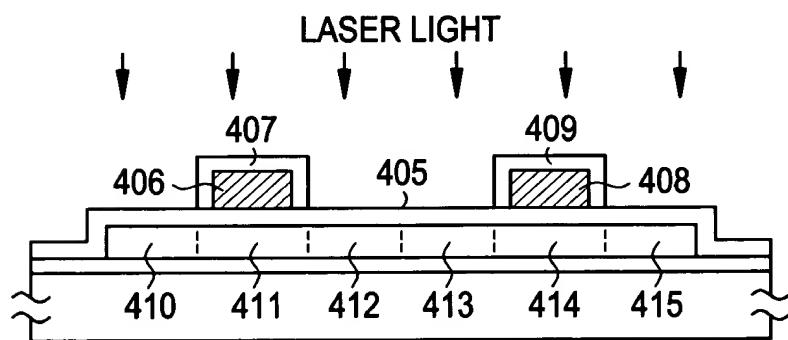
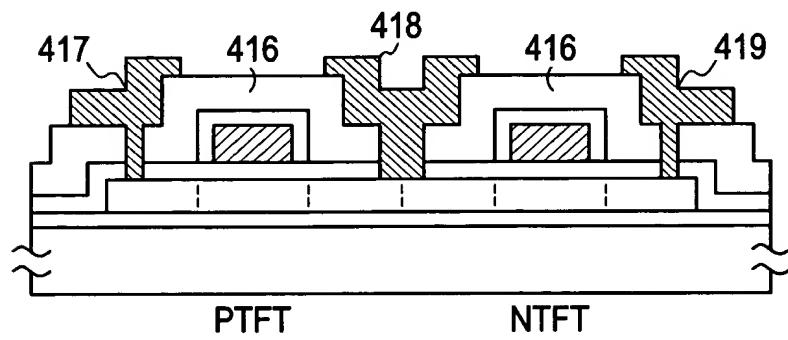


FIG. 7D





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FIG. 8A

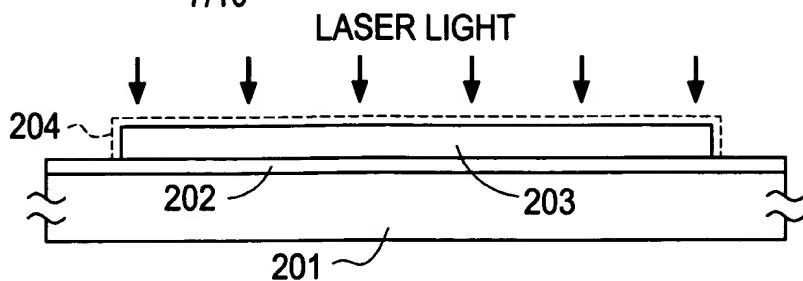


FIG. 8B

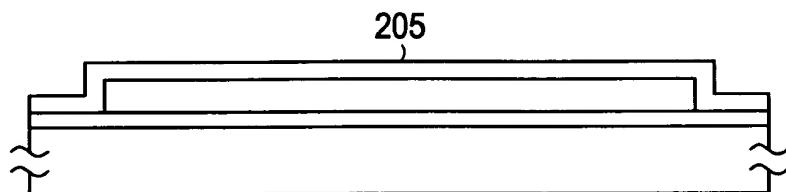


FIG. 8C

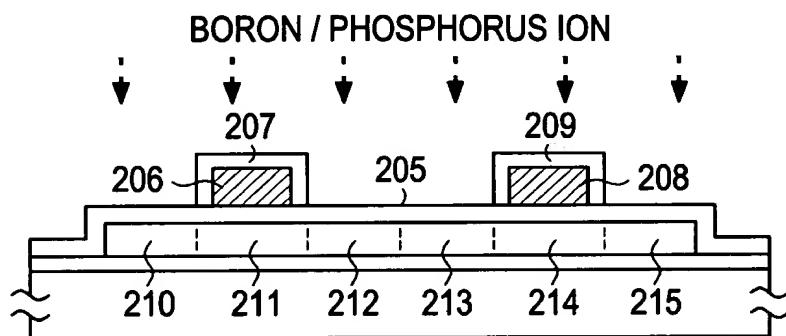


FIG. 8D

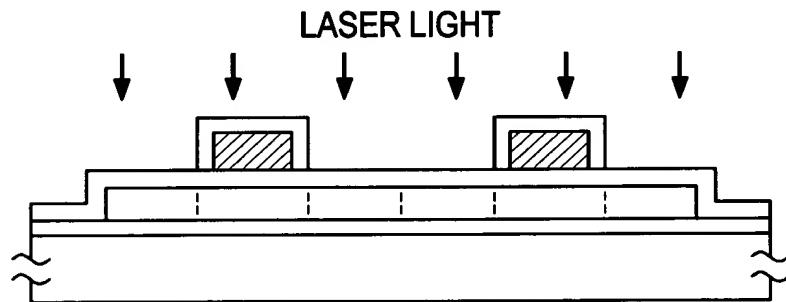
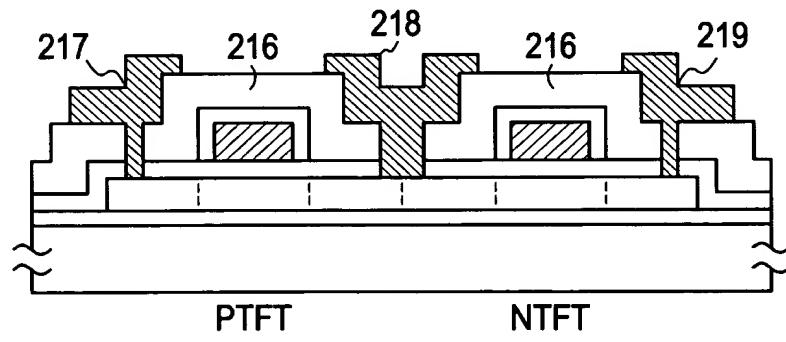


FIG. 8E





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FIG. 9A

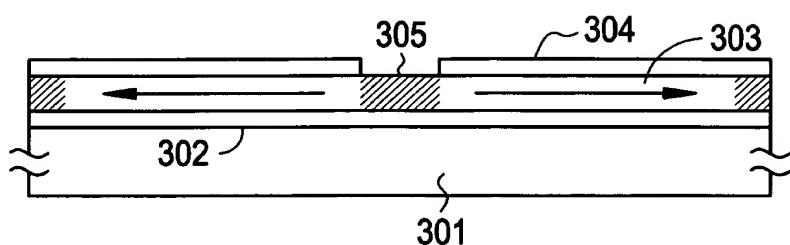


FIG. 9B

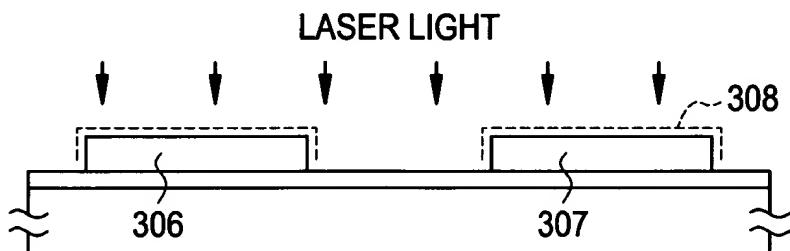


FIG. 9C

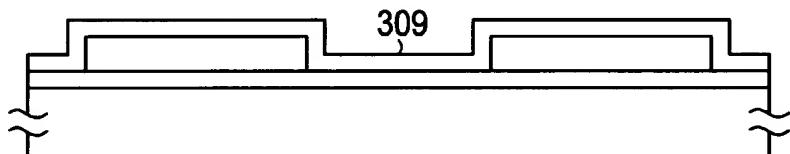


FIG. 9D

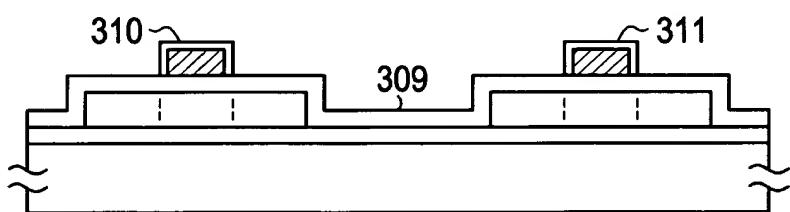
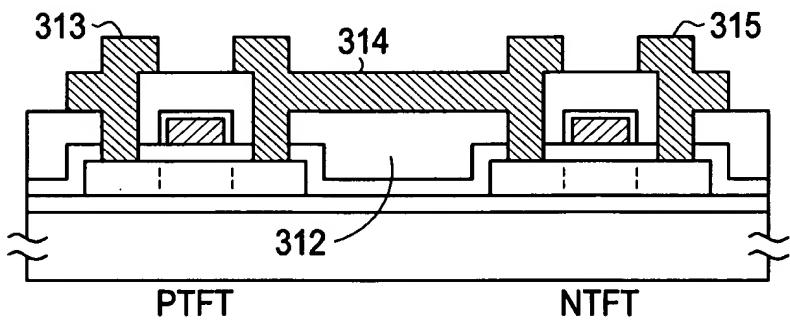


FIG. 9E





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FIG. 10A

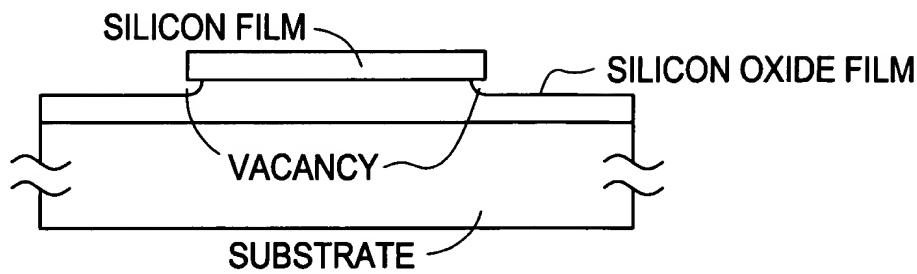


FIG. 10B

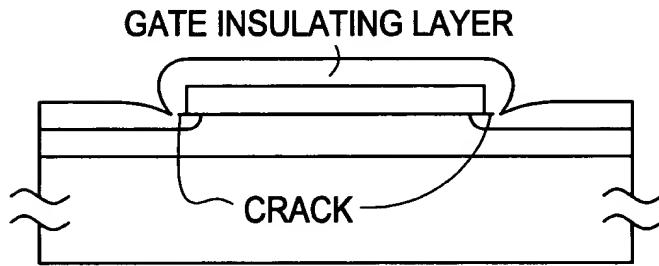
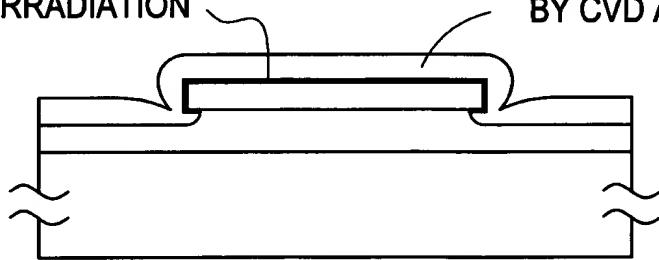


FIG. 10C

SILICON OXIDE FILM FORMED
BY LASER IRRADIATION

INSULATING LAYER FORMED
BY CVD AND SO ON



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FIG. 11

